

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 11-309354

(43)Date of publication of application : 09.11.1999

(51)Int.Cl.

B01D 69/12

B01D 61/04

B01D 69/02

(21)Application number : 10-132757

(71)Applicant : NITTO DENKO CORP

(22)Date of filing : 27.04.1998

(72)Inventor : TANAKA KAZUO

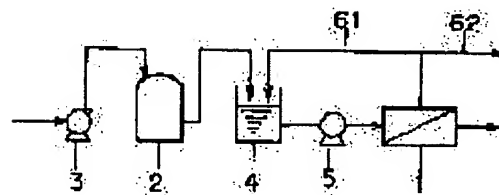
HACHISUGA HISAO

(54) PURE WATER PRODUCING SYSTEM

(57)Abstract:

PROBLEM TO BE SOLVED: To keep the amount of filtrate from a reverse osmosis membrane module sufficiently stable irrespective the elution of polymeric organic substances from an ion exchange resin apparatus by forming a surface potential reducing thin film on the membrane surface of the module.

SOLUTION: An ion exchange resin apparatus 2 is installed in the preceding stage of a reverse osmosis membrane module 1, raw water is supplied to the apparatus 2 by a liquid sending pump 3, and deionized water from the apparatus 2 is stored in an intermediate tank 4. The liquid in the tank 4 is supplied to the module 1 by a liquid sending pump 5. In this process, to prevent the attraction of eluted organic substances from the apparatus 2 to the membrane surface of the module 1 by an electrical surface phenomenon, a surface potential reducing thin film is formed on the surface of the reverse osmosis membrane. In this way, pure water can be produced in a stable flow rate.



LEGAL STATUS

[Date of request for examination]

08.11.2004

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office